



ASN Module (mandatory)
Academic Skills Development
(Scientific Communication)

Prof. R. Goldhahn
(*Department Material Physics*)

Modules and time schedule

		Specialization phase						Research phase						Examination schedule			
		1st semester			2nd semester			3rd semester			4th semester			SWS	CP	LN	PF
		19		30	17		30	13		30	0		30	49	120		
No	Compulsory modules ¹	SWS	Kind	CP	SWS	Kind	CP	SWS	Kind	CP	SWS	Kind	CP				
1	Entrance Harmonization Course ¹ 1/2	3	V+Ü	5										3	5		M,K ⁵
2	Entrance Harmonization Course ¹ 2/2	3	V+Ü	5										3	5		M,K ⁵
3	Solid-state physics	3	V+Ü	5										3	5		M,K ⁵
4	Semiconductor quantum structures				3	V+Ü	5							3	5		M,K ⁵
5	Semiconductor Devices I				3	V+Ü	5							3	5		M,K ⁵
6	Semiconductor Devices II							3	V+Ü	5				3	5		M,K ⁵
7	Semiconductor Process Technologies				2	V	5							2	5		M,K ⁵
8	Advanced semiconductor characterization				3	V+S	5							3	5		M,K ⁵
9	Advanced electronic circuits							3	V+Ü	5				3	5		M,K ⁵
10	Machine learning	4	V+Ü	5										4	5		M,K ⁵
11	Cleanroom lab course				3	P	5							3	5	*	ÜL
12	Academic Skills Development							4	S	5				4	5	*	SV
13	Introduction to Research								Wip	10				0	10	*	SV
14	Master's thesis												30	0	30		
	Compulsory electable modules³													6	10		
15	Physical/Technical Module 1	3	V+Ü	5										3	5		M,K ⁵
16	Physical/Technical Module 2				3	V+Ü	5							3	5		M,K ⁵
	Non-technical electable module⁴													6	10		
17	Non-technical module 1	3	V+Ü	5										3	5		M,K ⁵
18	Non-technical module 2							3	V+Ü	5				3	5		M,K ⁵

Aims, content. examination

- Participants acquire knowledge in current research topics by **studying available literature** and **convert** that knowledge **into an introductory presentation** for a scientific audience.
- They **prepare themselves** to be able to discuss relevant scientific aspects of their talk.
- Thereby, students become mature of free speech in scientific discussions, conferences, meetings and workshops.
- **Current topics of research**
- **Presentation and discussion of current research topics (30 min)**

NP 01: Nobel Prize in Physics 1971

Dennis Gábor

... "for his invention and development of the holographic method"



NP 02: Nobel Prize in Physics 1985

Klaus von Klitzing

... "for the discovery of the quantized Hall effect"



NP 03: Nobel Prize in Physics 1987

Georg Bednorz, Karl Alexander Müller

... "for their important break-through in the discovery of superconductivity in ceramic materials"



NP 04: Nobel Prize in Physics 1989

Wolfgang Paul, Hans Georg Dehmelt

... "for the development of the ion trap technique"

NP 05: Nobel Prize in Physics 1997

Steven Chu, Claude Cohen-Tannoudji, William Daniel Phillips

..."for development of methods to cool and trap atoms with laser light."



NP 06: Nobel Prize in Physics 1998

Robert Betts Laughlin, Horst Ludwig Störmer, Daniel Chee Tsui
... "for their discovery of a new form of quantum fluid with fractionally charged excitations"



NP 07: Nobel Prize in Physics 2001

Eric Allin Cornell, Wolfgang Ketterle, Carl Edwin Wieman

... "for the achievement of Bose–Einstein condensation in dilute gases of alkali atoms, and for early fundamental studies of the properties of the condensates"



NP 08: Nobel Prize in Physics 2005

John Lewis Hall, Theodor Hänsch

... "for their contributions to the development of laser-based precision spectroscopy, including the optical frequency comb technique"



Albert Fert, Peter Grünberg

... "for the discovery of giant magnetoresistance"



NP 10: Nobel Prize in Physics 2010

Andre Geim, Konstantin Novoselov

...**"for groundbreaking experiments regarding the two-dimensional material graphene"**



NP 11: Nobel Prize in Physics 2014

Isamu Akasaki, Hiroshi Amano, Shuji Nakamura

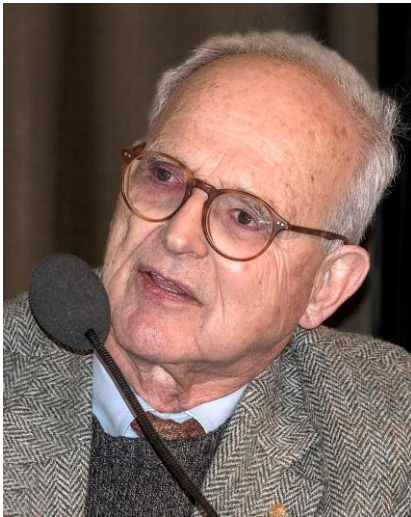
..."for the invention of efficient blue light-emitting diodes which has enabled bright and energy-saving white light sources"



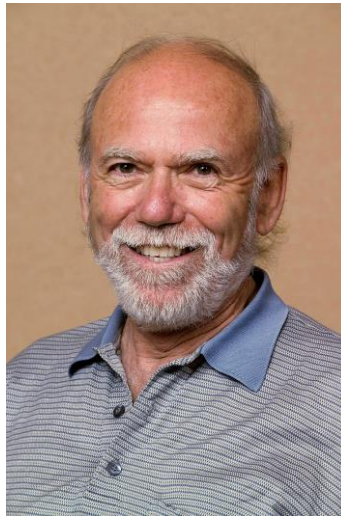
NP 12: Nobel Prize in Physics 2017

Rainer Weiss, Barry Barish, Kip Thorne

..."for decisive contributions to the LIGO detector and the observation of gravitational waves"



R. Goldhahn



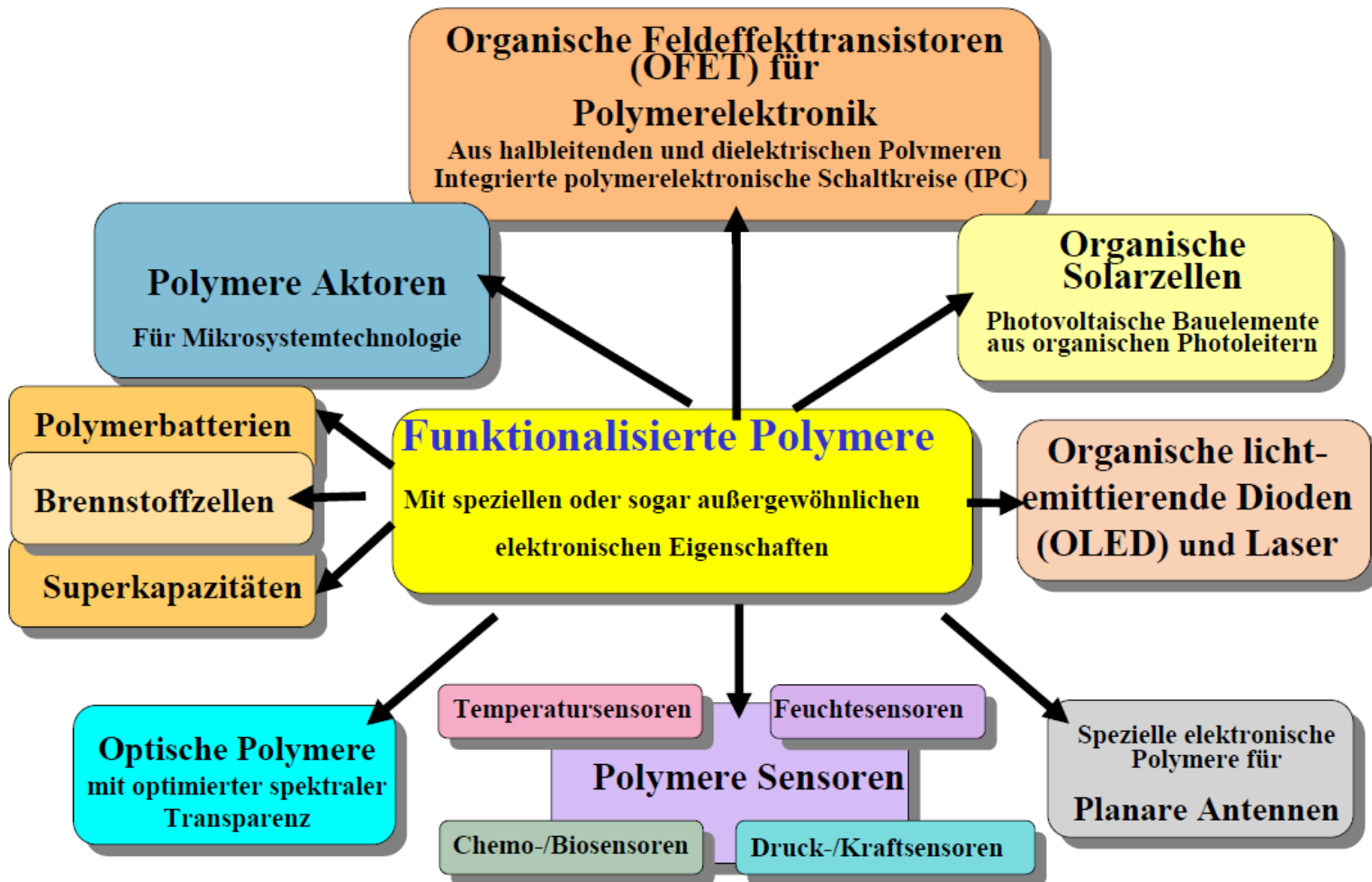
WS 2024/25



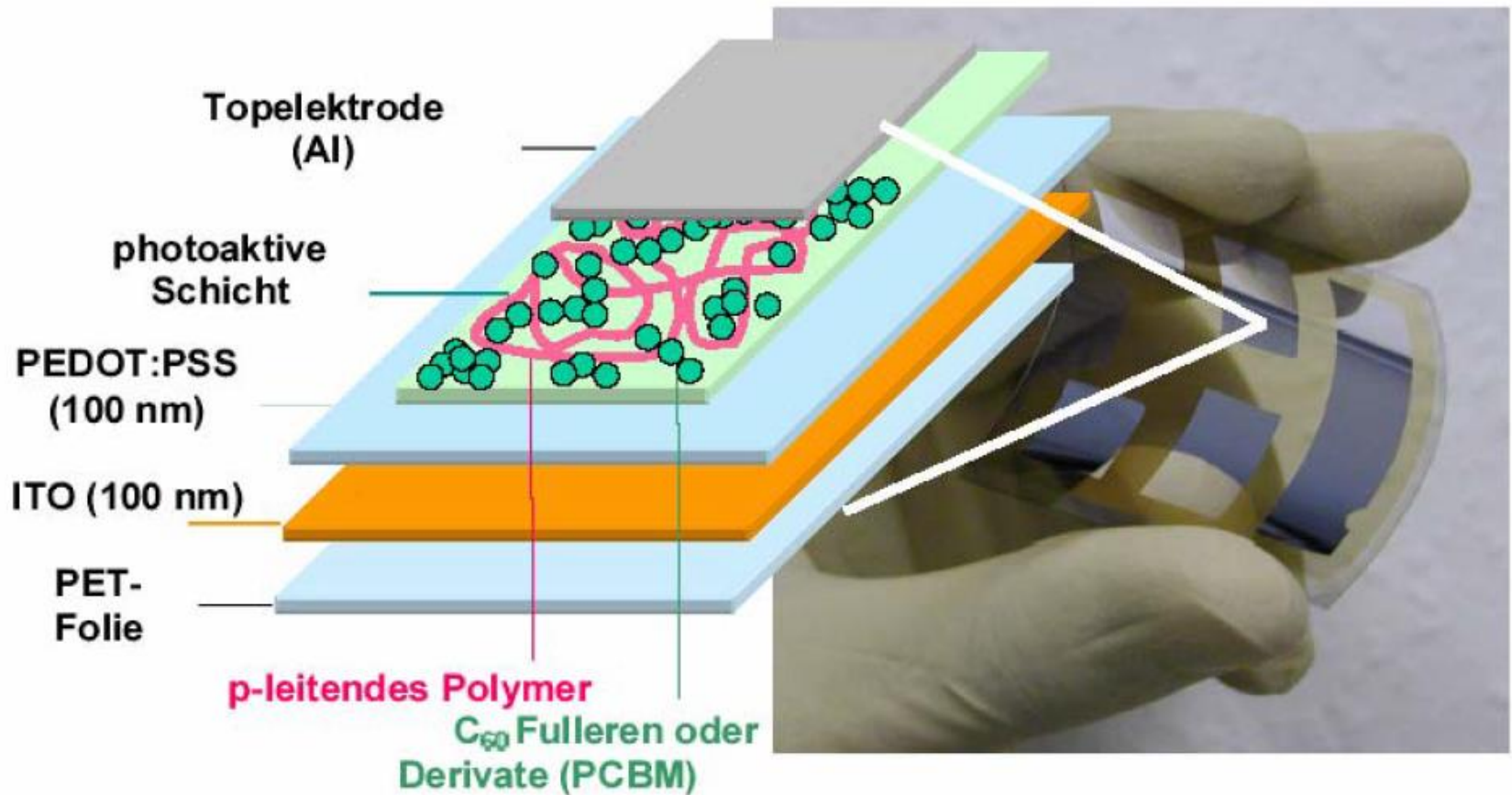
Academic Skills Development

NP 13: Nobel Prize in Chemistry 1996 and 2000

Basis for “organic” electronics



Prinzip der polymeren Solarzelle



NP 15: Nobel Prize in Chemistry 1996

Robert F. Curl Jr., Sir Harold W. Kroto, Richard E. Smalley

... "for their discovery of fullerenes"



NP 16: Nobel Prize in Chemistry 2000

Alan J. Heeger, Alan G. MacDiarmid, Hideki Shirakawa

... "for their discovery and development of conductive polymers"



MOSFETs with Stacked 2D Nanosheet Channels – An Auspicious Option to Delay “Forever”

F. Schwierz¹, M. Ziegler¹, and J. J. Liou²

¹Technische Universität Ilmenau, Germany, ²North Minzu University, Yinchuan, China

- **Introduction**
- **CMOS Scaling Trends and Moore’s Law**
- **The Four Stages of CMOS Scaling**
- **MOSFETs with Stacked 2D Nanosheet Channels**
- **Conclusion**

Perspective


The future transistors

<https://doi.org/10.1038/s41586-023-06145-x>

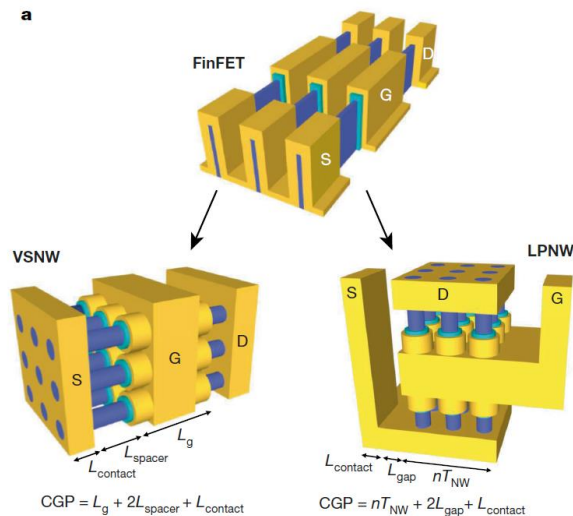
Received: 19 August 2020

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Published online: 16 August 2023

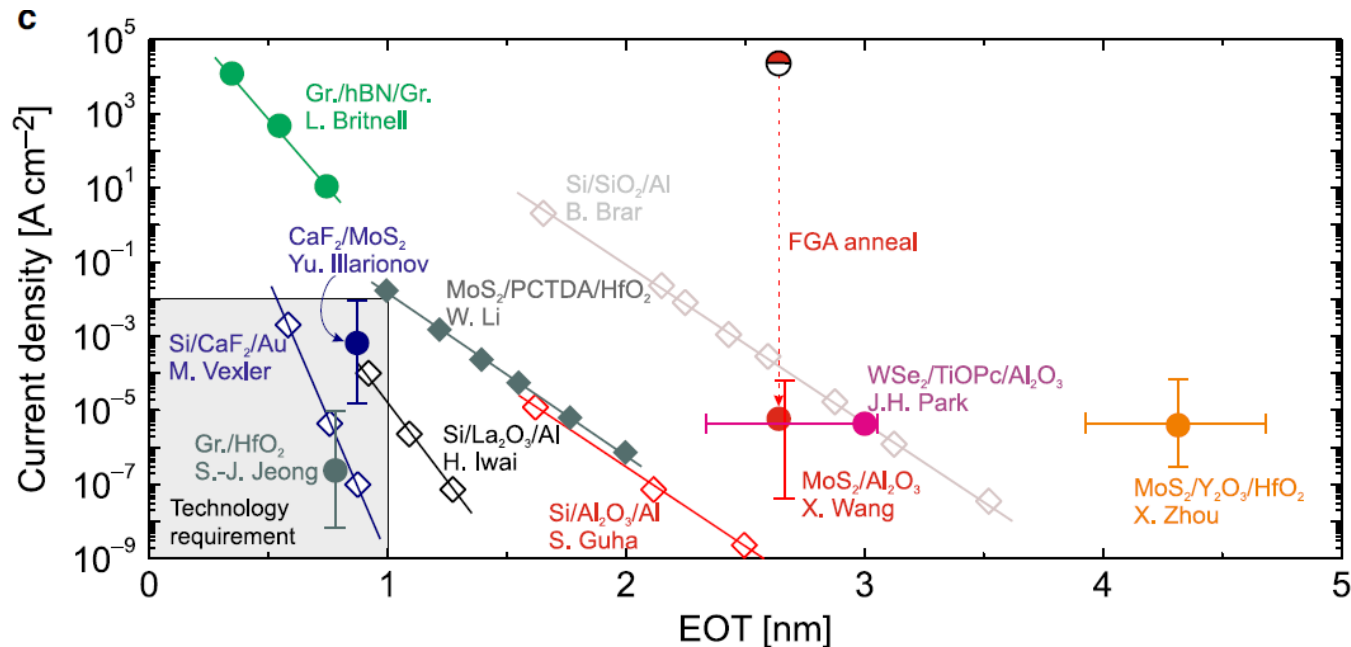
 Check for updatesWei Cao¹, Huiming Bu², Maud Vinet³, Min Cao⁴, Shinichi Takagi⁵, Sungwoo Hwang⁶,
Tahir Ghani⁷ & Kaustav Banerjee¹✉

The metal–oxide–semiconductor field-effect transistor (MOSFET), a core element of complementary metal–oxide–semiconductor (CMOS) technology, represents one of the most momentous inventions since the industrial revolution. Driven by the requirements for higher speed, energy efficiency and integration density of integrated-circuit products, in the past six decades the physical gate length of



Insulators for 2D nanoelectronics: the gap to bridge

Yury Yu. Illarionov ^{1,2}✉, Theresa Knobloch ¹, Markus Jech¹, Mario Lanza ³,
Deji Akinwande ⁴, Mikhail I. Vexler², Thomas Mueller⁵, Max C. Lemme ^{6,7},
Gianluca Fiori⁸, Frank Schwierz⁹ & Tibor Grasser ¹✉




Molybdenum disulfide transistors with enlarged van der Waals gaps at their dielectric interface via oxygen accumulation

Received: 4 March 2022

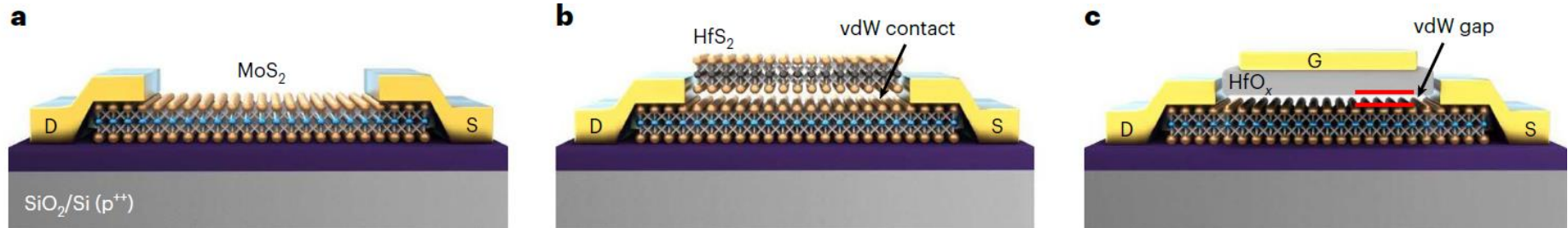
Accepted: 21 October 2022

Published online: 5 December 2022

 Check for updates




Pengfei Luo^{1,2}, Chang Liu¹, Jun Lin¹, Xinpei Duan¹, Wujun Zhang¹, Chao Ma¹, Yawei Lv¹, Xuming Zou^{1,2}, Yuan Liu¹, Frank Schwierz³, Wenjing Qin^{1,4}, Lei Liao^{1,2}, Jun He⁵ & Xingqiang Liu^{1,2,6}

Two-dimensional molybdenum disulfide (MoS_2) is a potential alternative channel material to silicon for future scaled transistors. Scaling down the gate dielectric and maintaining a high-quality interface is challenging with such materials, because the atomic thickness of MoS_2 makes it sensitive to defects common in amorphous gate oxides such as hafnium oxide (HfO_x).



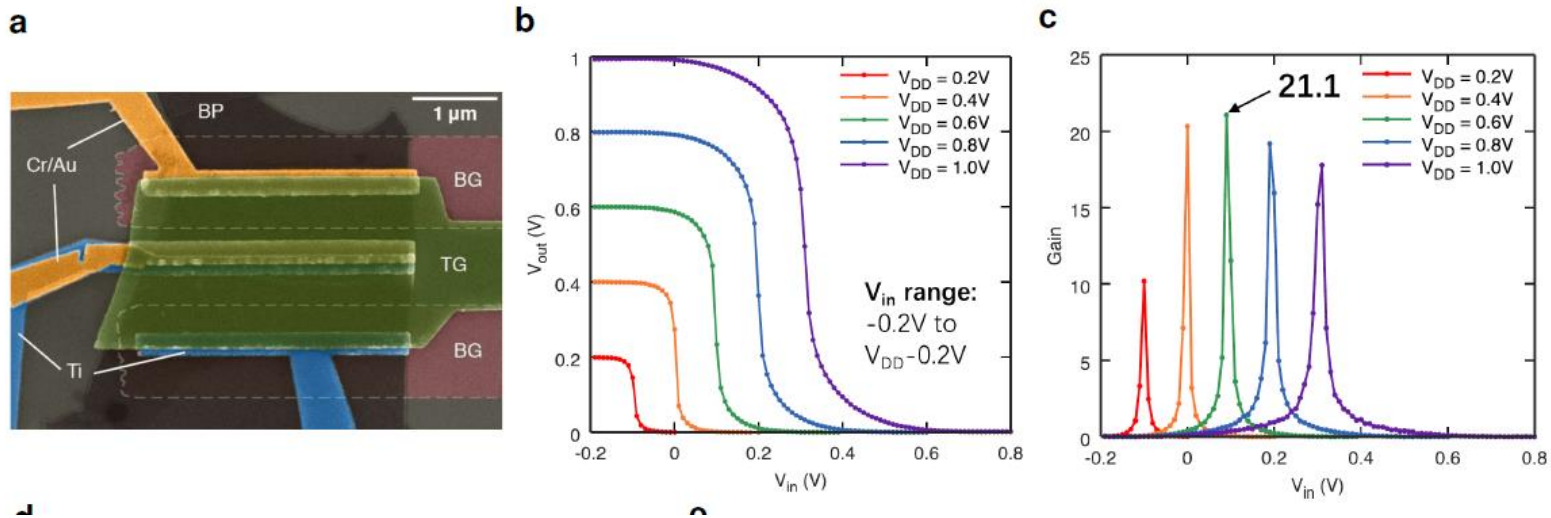
Review

Challenges for Nanoscale CMOS Logic Based on Two-Dimensional Materials

Theresa Knobloch ^{*} , Siegfried Selberherr  and Tibor Grasser 

Institute for Microelectronics, TU Wien, Gußhausstraße 27–29/E360, 1040 Vienna, Austria

* Correspondence: knobloch@iue.tuwien.ac.at



REVIEW

National Science Review

11: nwae008, 2024

<https://doi.org/10.1093/nsr/nwae008>

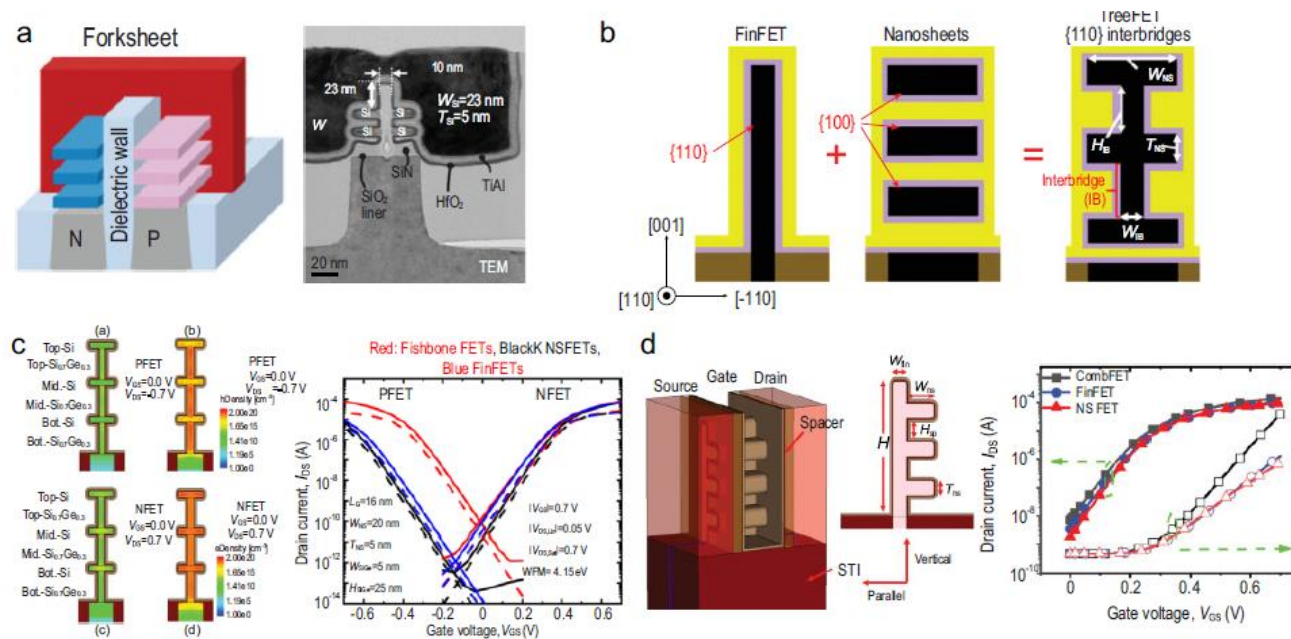
Advance access publication 5 January 2024

INFORMATION SCIENCE

Special Topic: Emerging Materials and Transistors for Integrated Circuits

New structure transistors for advanced technology node CMOS ICs

Qingzhu Zhang^{1,2,†}, Yongkui Zhang^{1,2,†}, Yanna Luo^{1,3} and Huaxiang Yin^{1,2,3,*}



Topical Review

Gallium nitride vertical power devices on foreign substrates: a review and outlook

Yuhao Zhang¹ , Armin Dadgar² and Tomás Palacios¹

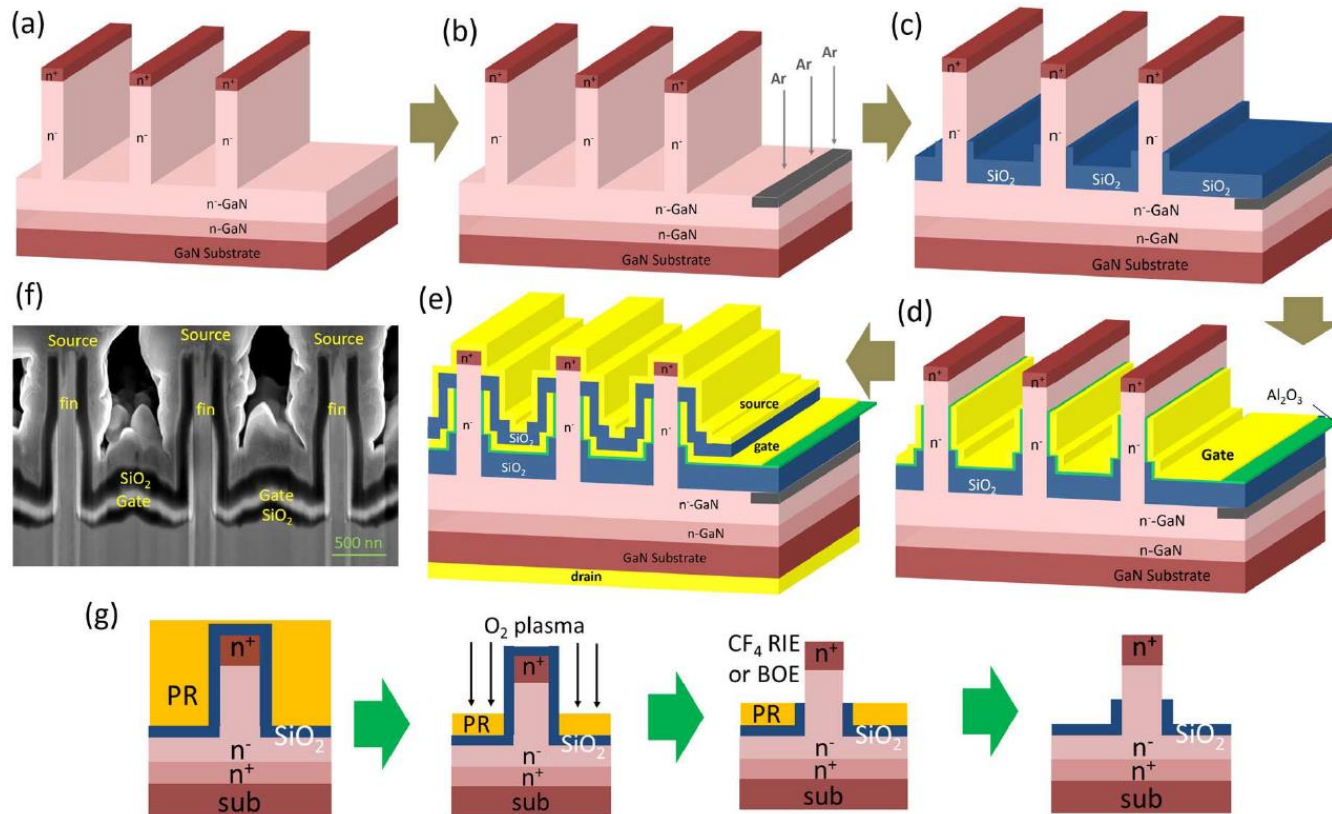
¹ Microsystems Technology Laboratories, Massachusetts Institute of Technology, Cambridge, MA 02139, United States of America

² Institute of Experimental Physics, Otto-von-Guericke-University Magdeburg, Magdeburg 39106, Germany

(Ultra)Wide-Bandgap Vertical Power FinFETs

Yuhao Zhang^{1b}, *Member, IEEE*, and Tomás Palacios^{1b}, *Fellow, IEEE*




(Invited Paper)



12: HEMT WBG

GaN-based power devices: Physics, reliability, and perspectives F FREE

Special Collection: [Wide Bandgap Semiconductor Materials and Devices](#)

Matteo Meneghini   ; Carlo De Santi  ; Idriss Abid; Matteo Buffolo  ; Marcello Cioni; Riyaz Abdul Khadar  ; Luca Nela  ; Nicolò Zagni  ; Alessandro Chini  ; Farid Medjdoub  ; Gaudenzio Meneghesso  ; Giovanni Verzellesi  ; Enrico Zanoni; Elison Matioli 



J. Appl. Phys. 130, 181101 (2021)

<https://doi.org/10.1063/5.0061354>

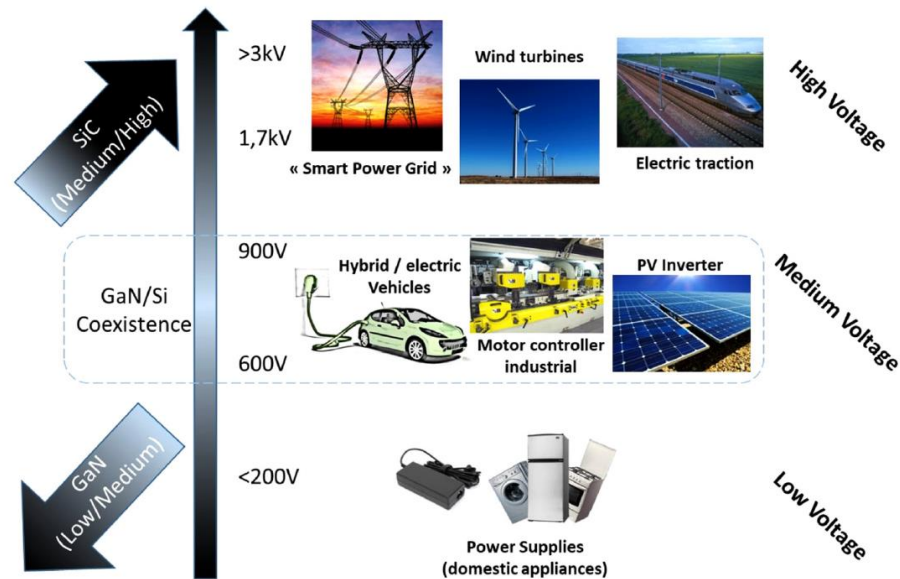


FIG. 14. Examples of applications using different voltage ranges.

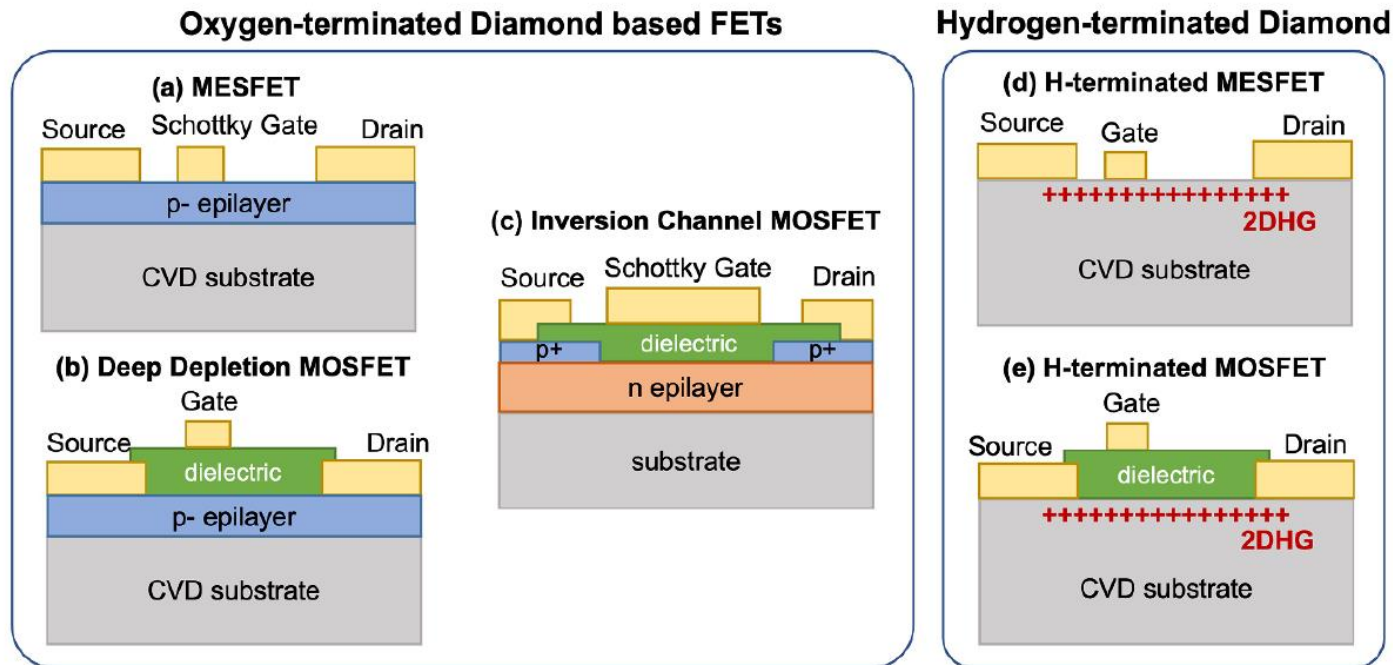
13: Power WBG Diamond and other

Journal of Physics: Materials

TOPICAL REVIEW

From wide to ultrawide-bandgap semiconductors for high power and high frequency electronic devices

Kelly Woo^{1,3} , Zhengliang Bian^{1,2,3} , Maliha Noshin^{1,3} , Rafael Perez Martinez¹ ,
Mohamadali Malakoutian¹ , Bhawani Shankar¹  and Srabanti Chowdhury^{1,*} 

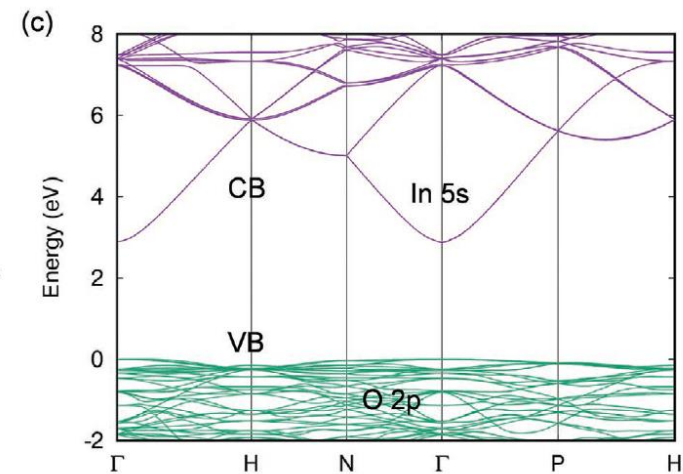
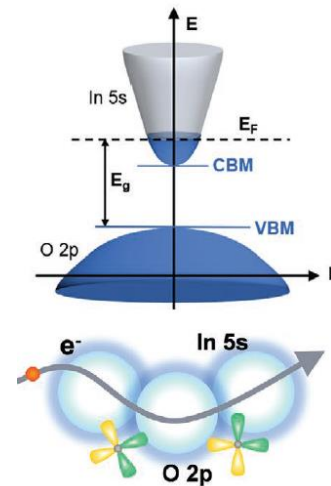


14: WBG: TCO for Optoelectronic Devices

REVIEW

Wide Bandgap Oxide Semiconductors: from Materials Physics to Optoelectronic Devices

Jueli Shi, Jiaye Zhang, Lu Yang, Mei Qu, Dong-Chen Qi, and Kelvin H. L. Zhang*








21: 2D Materials

RESEARCH ARTICLE | SEPTEMBER 16 2024

MOS-structured MoS₂/GaN Schottky barrier diodes with high on/off current ratio and low threshold voltage ✓

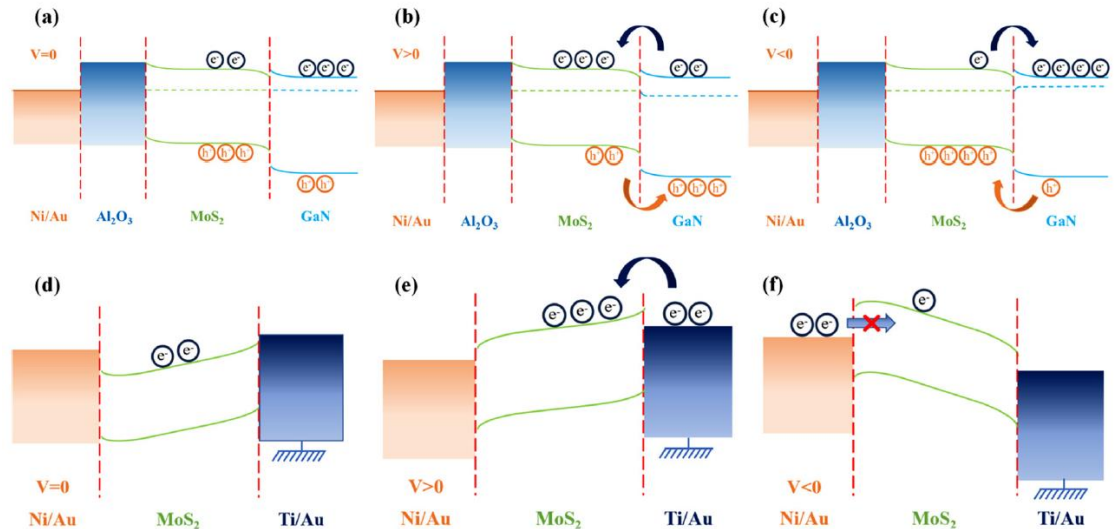
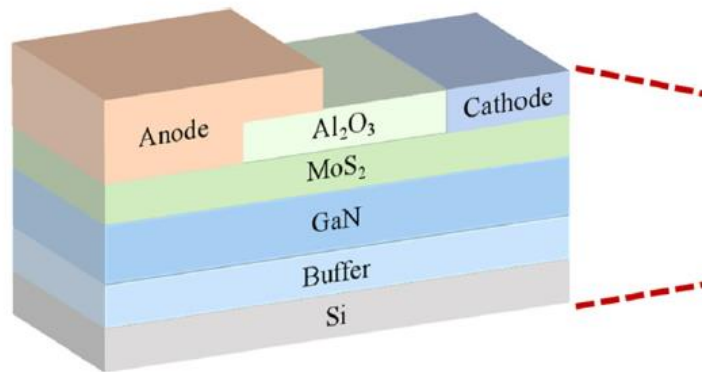
Special Collection: [Critical Issues on the 2D-material-based field-effect transistors](#)

Runjie Zhou ; Wenliang Wang  ; Guoqiang Li  



Appl. Phys. Lett. 125, 122103 (2024)

<https://doi.org/10.1063/5.0231505>



21: 2D Materials

RESEARCH ARTICLE | SEPTEMBER 09 2024

Fabrication of graphene field effect transistors on complex non-planar surfaces

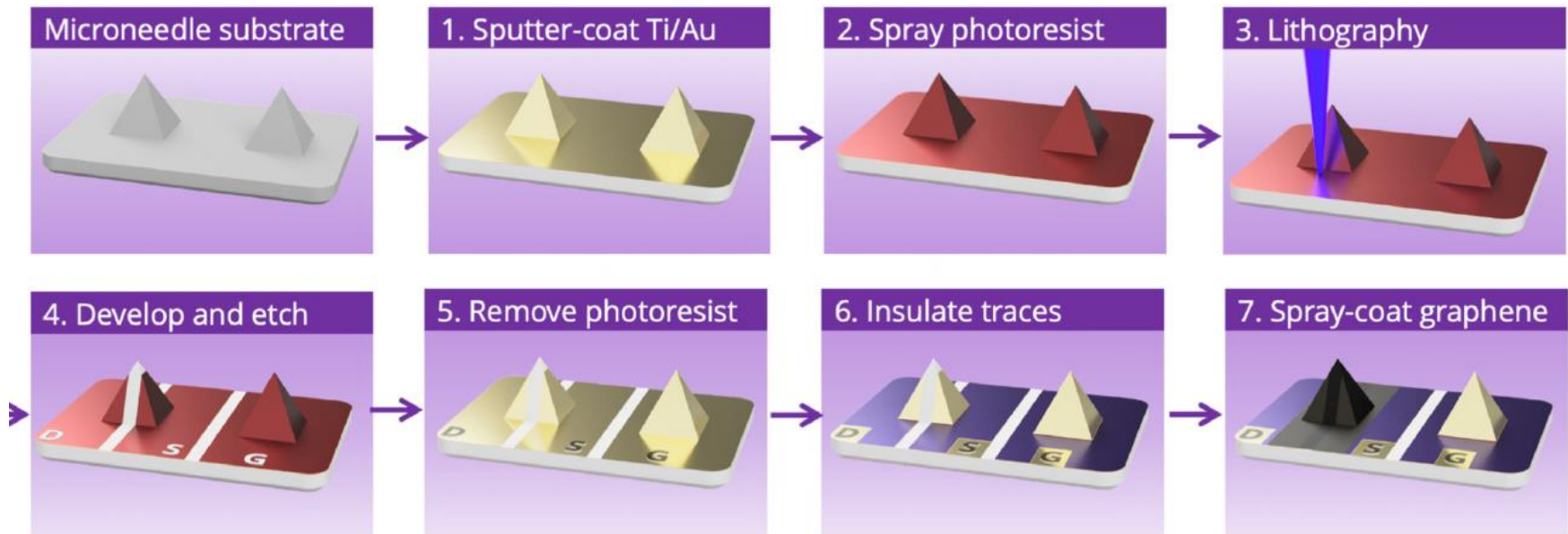
Special Collection: [Critical Issues on the 2D-material-based field-effect transistors](#)

M. Holicky  ; B. Fenech-Salerno  ; A. E. G. Cass  ; F. Torrisi  



Appl. Phys. Lett. 125, 113301 (2024)

<https://doi.org/10.1063/5.0226780>



31: Photonic Metasurfaces Roadmap

Roadmap on photonic metasurfaces

Cite as: Appl. Phys. Lett. **124**, 260701 (2024); doi: 10.1063/5.0204694

Submitted: 22 February 2024 · Accepted: 18 May 2024 ·

Published Online: 28 June 2024



View Online






Export Citation



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Sebastian A. Schulz,^{1,a)}  Rupert. F. Oulton,^{2,a)}  Mitchell Kenney,^{3,a)}  Andrea Alù,^{4,5}  Isabelle Staude,⁶ 
Ayesheh Bashiri,⁶  Zlata Fedorova,⁶  Radoslaw Kolkowski,⁷  A. Femius Koenderink,⁸  Xiaofei Xiao,² 
John Yang,²  William J. Peveler,⁹  Alasdair W. Clark,¹⁰  George Perrakis,¹¹  Anna C. Tasolamprou,¹² 
Maria Kafesaki,^{11,13}  Anastasiia Zaleska,¹⁴  Wayne Dickson,¹⁴  David Richards,¹⁴  Anatoly Zayats,¹⁴ 
Haoran Ren,¹⁵  Yuri Kivshar,¹⁶  Stefan Maier,^{15,17}  Xianzhong Chen,¹⁸  Muhammad Afnan Ansari,¹⁸ 
Yuhui Gan,¹⁹  Arseny Alexeev,²⁰  Thomas F. Krauss,²¹  Andrea Di Falco,¹⁹  Sylvain D. Gennaro,²² 
Tomás Santiago-Cruz,²³  Igal Brener,²³  Maria V. Chekhova,²⁴  Ren-Min Ma,²⁵  Viola V. Vogler-Neuling,²⁶ 
Helena C. Weigand,²⁷  Ulle-Linda Talts,²⁷  Irene Occhiodori,²⁷  Rachel Grange,²⁷  Mohsen Rahmani,²⁸ 
Lei Xu,²⁸  S. M. Kamali,²⁹  E. Arababi,³⁰  Andrei Faraon,³¹  Anthony C. Harwood,²  Stefano Vezzoli,²
Riccardo Sapienza,²  Philippe Lalanne,³²  Alexandre Dmitriev,³³  Carsten Rockstuhl,^{34,35} 
Alexander Sprafke,³⁶  Kevin Vynck,³⁷  Jeremy Upham,^{38,39}  M. Zahirul Alam,^{38,39}  Israel De Leon,^{40,41} 
Robert W. Boyd,^{38,39}  Willie J. Padilla,⁴²  Jordan M. Malof,⁴³  Aloke Jana,⁴⁴  Zijin Yang,⁴⁵  Rémi Colom,⁴⁶
Qinghua Song,⁴⁵  Patrice Genevet,⁴⁴  Karim Achouri,⁴⁷  Andrey B. Evlyukhin,^{48,49}  Ulrich Lemmer,^{50,51} 
and Ivan Fernandez-Corbaton³⁵ 

Low-dimensional wide-bandgap semiconductors for UV photodetectors

Ziqing Li^{1,3} , Tingting Yan^{2,3} & Xiaosheng Fang^{1,2}  

41: Emerging metal oxides: Review

APPLIED PHYSICS REVIEWS 5, 011301 (2018)

APPLIED PHYSICS REVIEWS

A review of Ga_2O_3 materials, processing, and devices

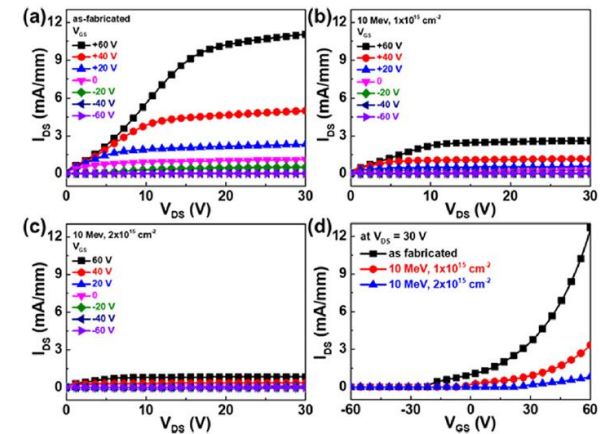
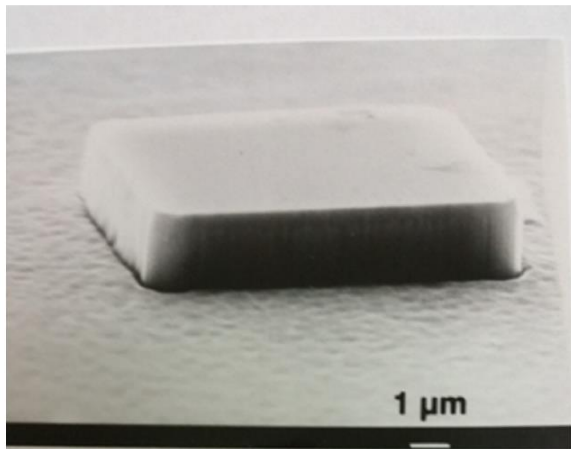
S. J. Pearton,^{1,a)} Jiancheng Yang,² Patrick H. Cary IV,² F. Ren,² Jihyun Kim,^{3,a)}
Marko J. Tadjer,⁴ and Michael A. Mastro⁴

¹Department of Materials Science and Engineering, University of Florida, Gainesville, Florida 32611, USA

²Department of Chemical Engineering, University of Florida, Gainesville, Florida 32611, USA

³Department of Chemical and Biological Engineering, Korea University, Seoul 02841, South Korea

⁴US Naval Research Laboratory, Washington, DC 20375, USA



42: Emerging metal oxides: Corundum structure

Japanese Journal of Applied Physics **62**, SF0803 (2023)

<https://doi.org/10.35848/1347-4065/acd125>

Progress in α -Ga₂O₃ for practical device applications

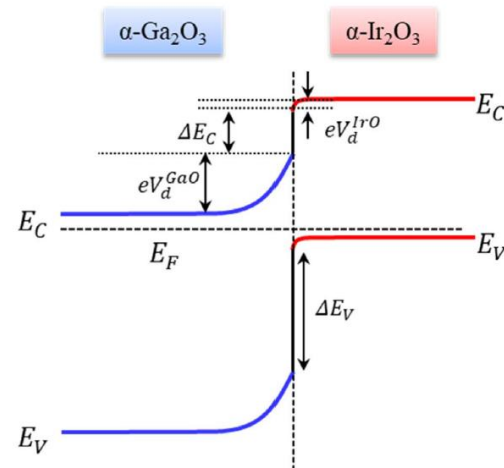
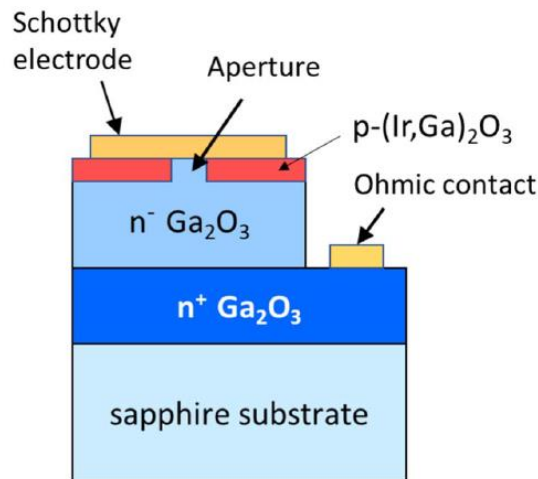
Kentaro Kaneko^{1,2*}, Shizuo Fujita³, Takashi Shinohe⁴, and Katsuhisa Tanaka²

¹Research Organization of Science and Technology, Ritsumeikan University, Kusatsu, Shiga 525-8577, Japan

²Department of Material Chemistry, Kyoto University, Nishikyo-ku, Kyoto 615-8510, Japan

³Office of Society-Academia Collaboration for Innovation, Kyoto University, Sakyo-ku, Kyoto 606-8501, Japan

⁴FLOSFIA Inc., Nishikyo-ku, Kyoto 615-8245, Japan



43_a: Emerging metal oxides: Growth β -Ga₂O₃


OPEN ACCESS

Applied Physics Express 17, 090101 (2024)

<https://doi.org/10.35848/1882-0786/ad6b73>

APEX REVIEW

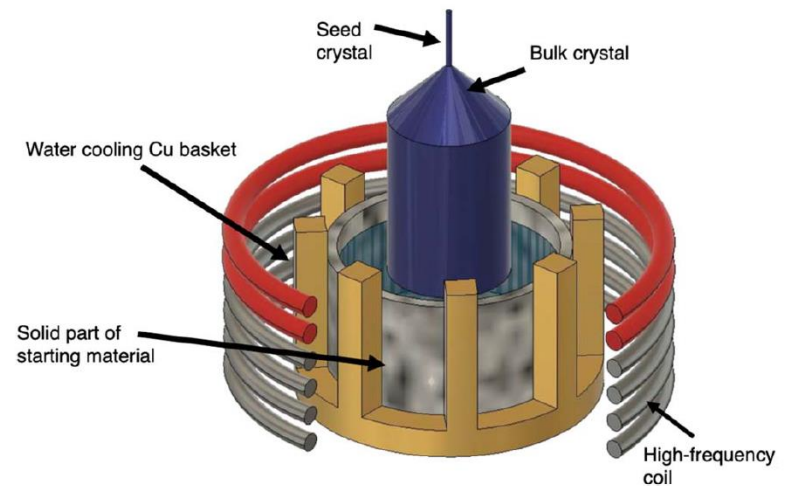
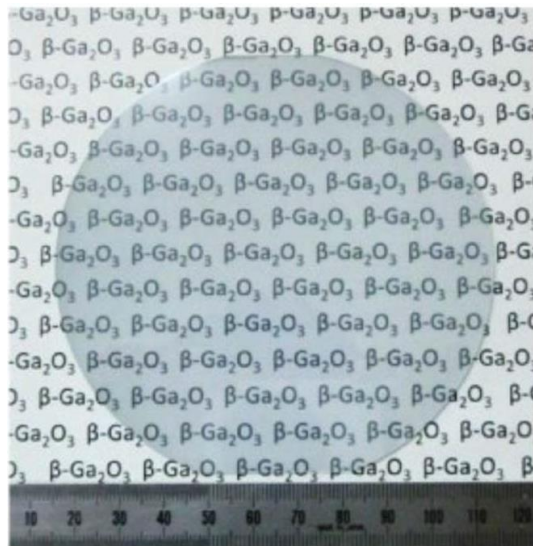
Prospects for β -Ga₂O₃: now and into the future

Kohei Sasaki 

Novel Crystal Technology, Inc., Sayama, Saitama 350-1328, Japan

*E-mail: sasaki@novelcrystal.co.jp

Received July 24, 2024; revised August 2, 2024; accepted August 5, 2024; published online September 30, 2024



43_b: Emerging metal oxides: Electronic devices β -Ga₂O₃


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Applied Physics Express 17, 090101 (2024)

<https://doi.org/10.35848/1882-0786/ad6b73>

APEX REVIEW

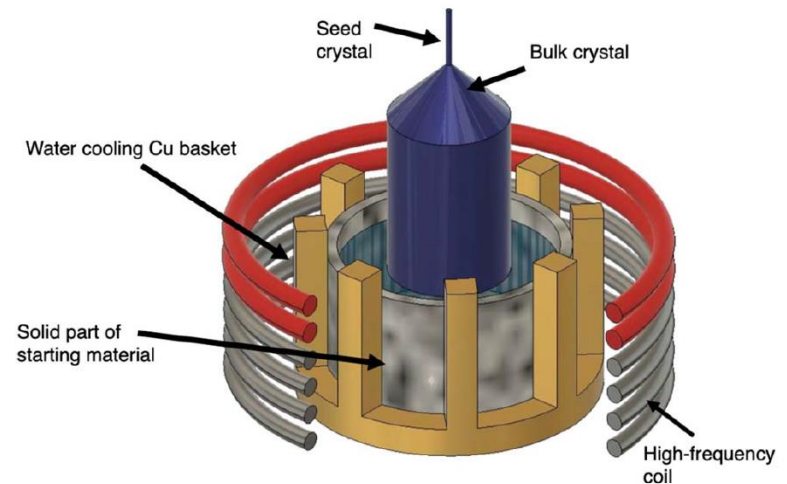
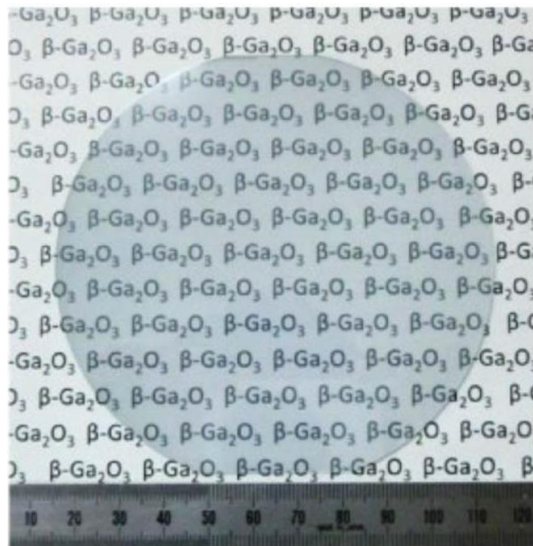
Prospects for β -Ga₂O₃: now and into the future

Kohei Sasaki 

Novel Crystal Technology, Inc., Sayama, Saitama 350-1328, Japan

*E-mail: sasaki@novelcrystal.co.jp

Received July 24, 2024; revised August 2, 2024; accepted August 5, 2024; published online September 30, 2024



41: Emerging metal oxides:
